## Silanes

An Isolable Radical Anion and Dianion of a Cyclotetrasilane: Synthesis and Structure of  $[Si\{1,2-(NEt)_2C_6H_4\}]_4^{-\cdot}$  and  $[Si\{1,2-(NEt)_2C_6H_4\}]_4^{2-**}$ 

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The stability of isolable N-heterocyclic silylenes<sup>[1,2]</sup> has its origin in a significant  $\pi$  delocalization in the five-membered ring of Si[N(tBu)CHCHNtBu] (**A**)<sup>[3]</sup> or the benzo-annulated

 $Si[1,2-(NCH_2tBu)_2C_6H_4]$  (**B**)<sup>[4]</sup> with incorporation of the formally empty silicon out-of-plane p orbital. [5,6] In contrast, the silylene Si[N(tBu)- $CH_2CH_2NtBu$ ] (C),<sup>[7]</sup> which lacks  $\pi$  delocalization is only marginally stable and converts into its stable tetramer. [8] But how important is the steric protection provided by the bulky tBu or CH<sub>2</sub>tBu groups in the stable silvlenes A and B, respectively, and what effect will a reduction of the size of the substituent at the nitrogen atom have on the stability of a two-coordinate silicon species? Herein we report 1) the reduction of the  $Cl_2Si[1,2-(NR)_2C_6H_4]$  (R = Et; 3) analogue of the silvlene precursor of **B** ( $R = CH_2tBu$ ) with potassium, 2) the synthesis of the first isolable and structurally characterized radical anion of a cyclotetrasilane,  $[Si\{1,2-(NEt)_2C_6H_4\}]_4^{-\bullet}$ , and 3) its dianion  $[Si\{1,2-(NEt)_2C_6H_4\}]_4^{2-}$ .

Reduction of  $\text{Cl}_2\text{Si}[1,2\text{-}(\text{NEt})_2\text{C}_6\text{H}_4]$  (3)<sup>[9]</sup> with potassium in THF at ambient temperature afforded a product mixture of the potassium salt of the radical anion  $\mathbf{1}^{-\bullet}$  and the dianion  $\mathbf{2}^{2-}$  (Scheme 1). Complex **1** could be isolated from the mixture as green crystals at  $-25\,^{\circ}\text{C}$  whereas the orange complex **2** was crystallized from DME.

The structure of  $\mathbf{1}^{[10]}$  shows the potassium cation solvent-separated from the cyclotetrasilane radical anion (Figure 1) whilst for the structure of  $\mathbf{2}^{[11]}$  the solvated potassium cations have  $\eta^2$ -coordination to the 3,3'-C atoms (C14, C15) of the *o*-phenylene ring (Figure 2). In both,  $\mathbf{1}$  and  $\mathbf{2}$ , the cyclotetrasilane ring lies on an inversion centre and the  $\{\text{Si}_4\}$  core is planar. The Si1–Si2 bond length in  $\mathbf{1}$  of 2.347(2) Å (see Table 1) is slightly shorter compared to Si–Si bond lengths

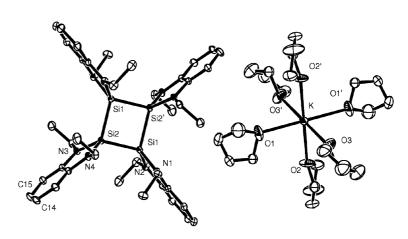


Figure 1. Molecular structure of 1 (thermal ellipsoids set at 20 % probability).

## Scheme 1.

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which are found in cyclopolysilanes (av.  $2.372 \text{ Å})^{[12]}$  or for tetrasilacyclobutanes ( $2.363-2.445 \text{ Å}).^{[13]}$  Even further reduction of the Si1–Si2 bond length is found for complex **2** (2.284(2) Å), which is close to the range of Si–Si double bonds ( $2.138-2.261 \text{ Å})^{[12]}$  and may also be compared to the Si–Si bonds in a *Z*-diaminodisilyldisilene (the tetramer of **C**;  $2.289 \text{ Å})^{[8]}$  or cyclotetrasilenes (2.174,  $2.257 \text{ Å}).^{[14,15]}$  The substantial shortening of the Si–Si bond in **1** and **2** can be

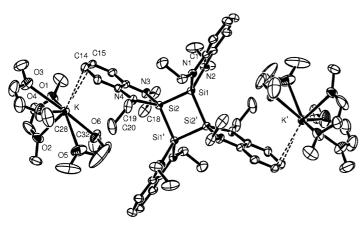


Figure 2. Molecular structure of 2 (thermal ellipsoids set at 20 % probability).

Table 1: Selected bond lengths [Å] and angles [°] of compounds 1 and 2.

Bond	1	2	Angle	1	2
Si1-Si2'	2.346(2)	2.284(2)	Si2'-Si1-Si2	90.27(6)	89.87(5)
Si1-Si2	2.347(2)	2.284(2)	Si1'-Si2-Si1	89.73 (6)	90.13(5)
Si1-N1	1.768(4)	1.814(3)	N1-Si1-N2	88.6(2)	85.2(2)
Si1-N2	1.775(4)	1.799(4)	N3-Si2-N4	88.6(2)	84.7(2)
Si2-N3	1.770(4)	1.807(3)			
Si2-N4	1.765(4)	1.812(3)			
K···C14 K···C15		3.137(5)			
KC12		3.266(5)			

attributed to the additional one or two electrons, respectively, which are delocalized in the  $Si_4$  ring.

ESR-spectroscopic analysis<sup>[16]</sup> (Figure 3a) of **1** ( $g_{iso}$  = 2.0025, a = 3.5 G) shows 15 of the 17 expected lines (2nI + 1, I = 1, n = 8) consistent with the electron being delocalized over the Si<sub>4</sub> ring and is in good agreement with the simulated spectrum (Figure 3b).

Alkali-metal reduction of a cyclosilane to obtain a radical anion is a long established method. A wide range of ESR spectroscopic analysis shows that the unpaired electron is

delocalized over the resulting cyclopolysilane ring.<sup>[17-19]</sup> All of these radical anions of cyclosilanes are labile and are only detected at low temperature. Persistent radical anions of ladder oligosilanes were reported recently.<sup>[20]</sup> The radical anion 1<sup>-1</sup> of complex 1 is the first thermally robust, crystalline and structurally characterized radical anion of a cyclopolysilane.

The proposed mechanism leading to  $\bf 1$  and  $\bf 2$  may involve pathways (a), (b) and/or (c) (Scheme 2). Precedence for pathway (a) is found in the reported formation of  $\bf 6$  and  $\bf 7$  (where (NN)Si= $\bf C$ )<sup>[21]</sup> by reduction of  $\bf C$  with Na/K or the formation of  $\bf 7$  (where (NN)Si= $\bf B$ ) by reduction of  $\bf B$  with potassium. Precedence for pathway (b) is the report that the transient silylene ( $tBu_3Si$ )SiCl inserts into the Si-Na bond of its precursor (tBuSi)SiCl<sub>2</sub>Na; in the present context this

corresponds to the insertion of **5** into the Si–K bond of **4** to form **8**. This insertion was found to proceed more readily than insertion into the Si–H bond of the common silylene trap Et<sub>3</sub>SiH and was accompanied by one or two further insertions of (*t*BuSi)SiCl into the Si–Na bond of the successive intermediates, which led, after elimination of NaCl, to the corresponding cyclosilanes (*t*BuSiSiCl)<sub>3</sub> and (*t*BuSiSiCl)<sub>4</sub>.<sup>[23]</sup> A third pathway (c) is possible, which is commonly suggested for the synthesis of cyclooligosilanes by reductive dehalogenation of halosilanes, which in this case would proceed by reaction of **4** with the dichlorosilane **3** to yield a 1,2-dichlorodisilane **10**. Successive metallation and reaction with **3** followed by elimination of NaCl would also lead to intermediate **9**.

Complex **2** can readily be converted into **1** by, for example, treatment with **3**. Attempts to isolate the neutral cyclotetrasilane [Si{1,2-(NEt)<sub>2</sub>C<sub>6</sub>H<sub>4</sub>}]<sub>4</sub> (cf., **9** in Scheme 2) have so far been unsuccessful, presumably owing

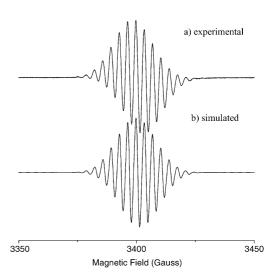


Figure 3. ESR spectrum of 1.

$$(NN)Si \stackrel{Cl}{\leftarrow} K \qquad (NN)Si \stackrel{K}{\leftarrow} K \qquad (NN)Si \stackrel{K$$

Scheme 2.

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to the readiness of  $[Si\{1,2-(NEt)_2C_6H_4]]_4$  to take up a single electron. Surprisingly, the reduction of  $Cl_2Si[1,2-(NR)_2C_6H_4]$  upon changing the substituent at N from R = Et to the bulkier iBu led to a similar formation of a cyclotetrasilane radical anion and dianion, which will be reported in the full paper. The neopentyl substituent  $(R = CH_2tBu)$  therefore seems ideally suited to provide steric protection for the silylene **B**.

## **Experimental Section**

1: Potassium (1.45 g, 0.037 mol) was added to a solution of **3** (4.85 g, 0.019 mol) in THF (150 mL) at ambient temperature. The mixture initially turned green and after stirring for 2 days to green brown. The mixture was filtered and the green residue was extracted with hot THF. The extract was concentrated and green crystals of compound **1** were obtained at -25 °C.

2: Potassium (3.5 g, 0.89 mol) was added to a solution of **3** (5.85 g, 0.022 mol) in THF (150 mL) at ambient temperature. The mixture initially turned green. The mixture was stirred for 5 days then filtered and the solvent was removed from the red-brown filtrate. The residue was crystallized from DME yielding orange crystals of compound **2** (4.9 g, 64%). <sup>1</sup>H NMR (300 MHz, [D]<sub>8</sub>THF):  $\delta$  = 1.05 (br,s, 6 H, CH<sub>3</sub>), 3.26 (dme), 3.42 (dme), 3.78 (br,d, 4H, CH<sub>2</sub>), 5.95 (m, 2H, phenyl), 6.09 ppm (m, 2H, phenyl). <sup>29</sup>Si{<sup>1</sup>H} NMR (99.3 MHz, [D]<sub>8</sub>THF):  $\delta$  = -45.2 ppm.

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- [10] Crystal data for 1:  $C_{64}$  H<sub>104</sub>KN<sub>8</sub>O<sub>6</sub>Si<sub>4</sub>,  $M_r$ =1233.01, specimen  $0.20\times0.05\times0.05$  mm³, monoclinic, space group  $P2_1$ /n (No. 14), a=18.2955(7), b=9.4645(4), c=20.0260(8) Å,  $\beta$ =91.757(2)°, U=3466.0(2) ų, Z=2,  $\mu$ =0.20 mm¹, T=173(2) K, 4775 unique reflections collected,  $R_1$ =0.069 for 3212 reflections with  $I>2\sigma(I)$ ,  $wR_2$ =0.174 for all reflections, Data collection KappaCCD, full-matrix least-squares refinement on  $F^2$ , SHELX-97. CCDC-218118 (1) and CCDC-218119 (2) contains the supplementary crystallographic data for this paper. These data can be obtained free of charge via www.ccdc.cam.ac.uk/conts/retrieving.html (or from the Cambridge Crystallographic Data Centre, 12 Union Road, Cambridge CB21EZ, UK; fax: (+44)1223-336-033; or deposit@ccdc.cam.ac.uk).
- [11] Crystal data for **2**:  $C_{64}H_{116}K_2N_8O_{12}Si_4$ ,  $M_r = 1380.21$ , specimen  $0.20 \times 0.20 \times 0.05 \text{ mm}^3$ , monoclinic, space group  $P2_1/n$  (No. 14),

- a = 12.7165(2), b = 19.0891(4), c = 17.2205(4) Å,  $\beta = 109.724(1)^{\circ}$ , U = 3934.96(14) Å<sup>3</sup>, Z = 2,  $\mu = 0.24$  mm<sup>-1</sup>, T = 173(2) K, 5295 unique reflections collected,  $R_1 = 0.0631$  for 3774 reflections with  $I > 2\sigma(I)$ ,  $wR_2 = 0.178$  for all reflections, Data collection KappaCCD, full-matrix least-squares refinement on  $F^2$ , SHELX-97. (CCDC reference number 218119.)
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